

Aerosol Jet Printing for Three Dimensional Interconnects

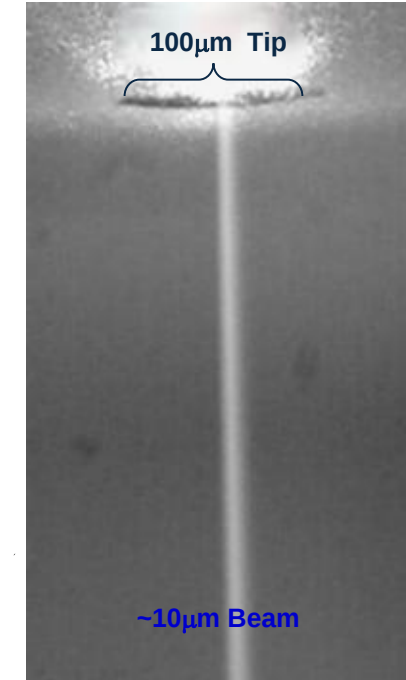
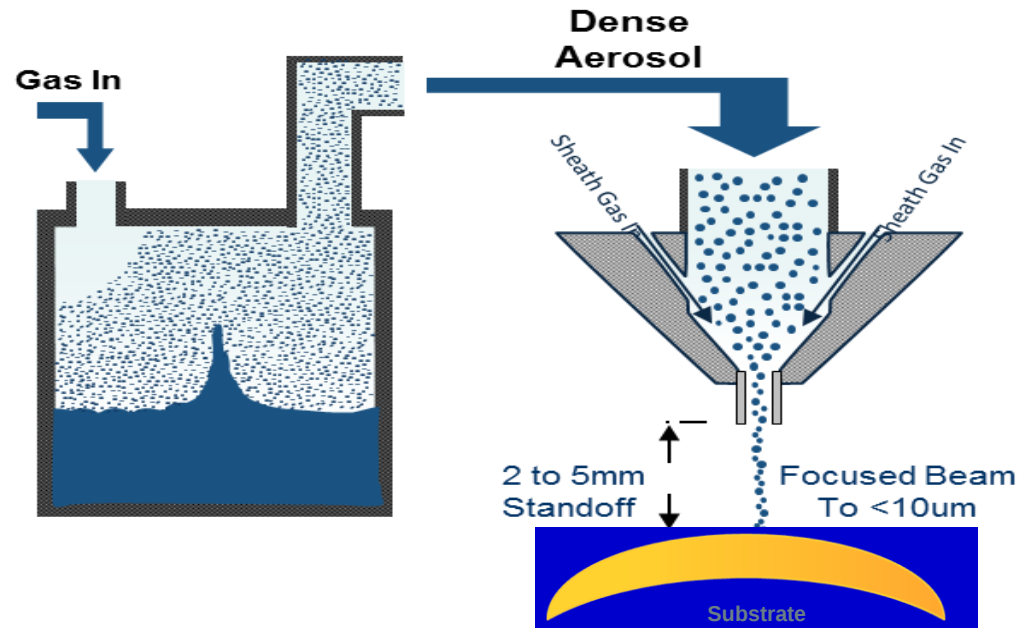
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Optomec, Inc

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Outline

- **Introduction to Aerosol Jet Printing**
- **Materials Compatibility**
- **Characteristics of Printed gold**
- **Role of Dielectric Support Materials**
- **3D Interconnect Printing**
- **Wirebonding on Printed Gold**

Aerosol Jet Process (Ultrasonics)



- 1 Atomize Liquid Electronic Material: conductive inks, dielectric, (1-12 cP)
- 2 Mist of 2 to 5 µm Ø highly dense, highly loaded droplets
- 3 Sheath gas surrounds and focuses particle beam
- 4 Continuous Flow Exits at 50m/s remains collimated for up to 5 mm
- 5 Print on planar and non planar substrates

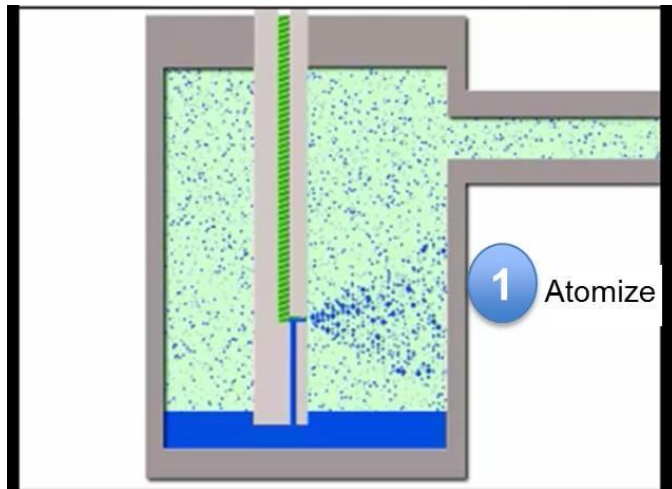
Common applications:

- Fine features with high density (10um/10um L/S)
- Thin films (50nm)
- Aqueous 'inks': acids, bases, CNTs, Graphine
- On-the-fly UV curing and laser sintering

3D Interconnect Printing

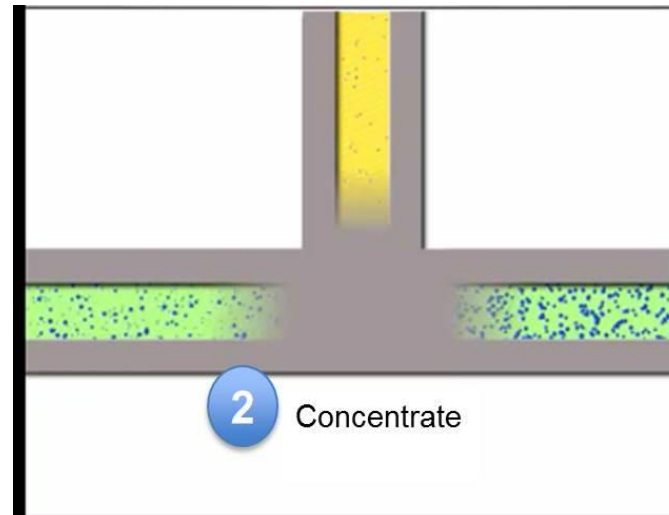


Aerosol Jet Process (Pneumatics)



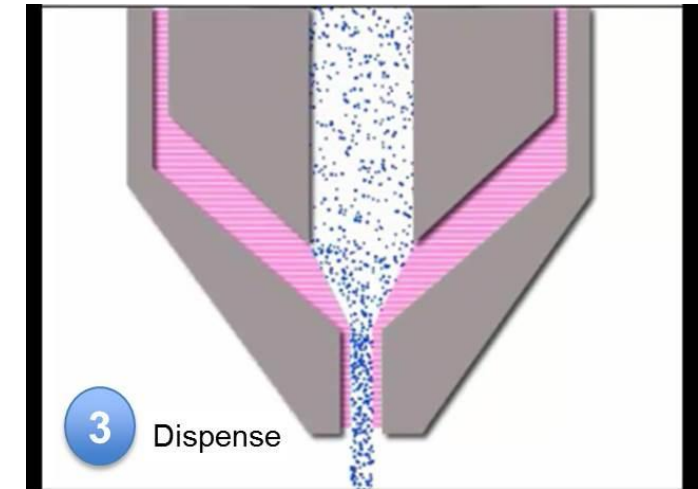
(1) Pneumatically atomize ink

- Small droplets 2 to 5 microns in diameter
- Supports many materials w/high solids loading
- 60wt% dispersions, all solids UV polymers
- Viscosity 1000+ cP



(2) Concentrate aerosol w/virtual impaction

- Remove excess gas
- Partially dry the droplets



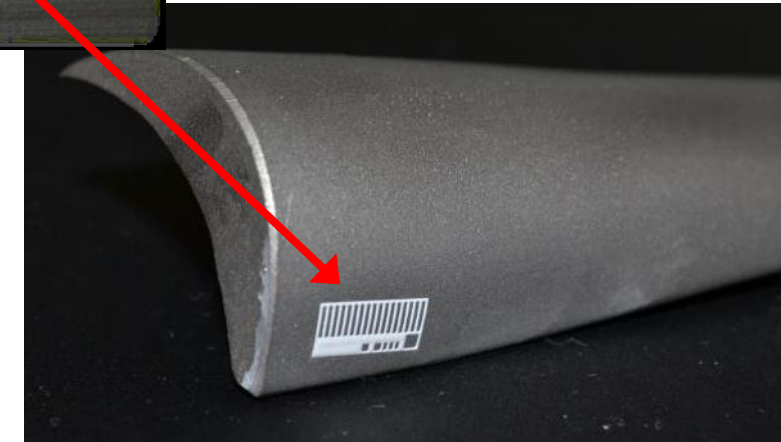
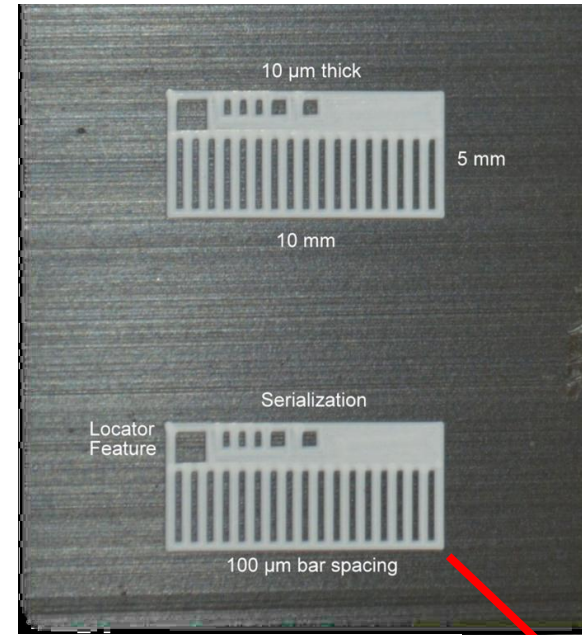
(3) Dispense aerosol

- Focus aerosol with sheath gas
- Prevents clogging
- High exit velocity 50 m/s
- Print on 2D and 3D surfaces

Enables printing of conventional screen print pastes

Creep Sensor for Predictive Maintenance

- Health Monitoring for High-Value Components
- High Temp (>1800°F) In-Situ Creep Sensors
 - Optical sensors detects fatigue and creep
 - Unique serialization for each gage
- Enabled by Aerosol Jet Printing
 - 3D Conformal Printing directly onto parts.
 - Digital input enables Serialization
 - Supports High Temp YSZ Ceramic Ink



Wide Range of Commercial Materials

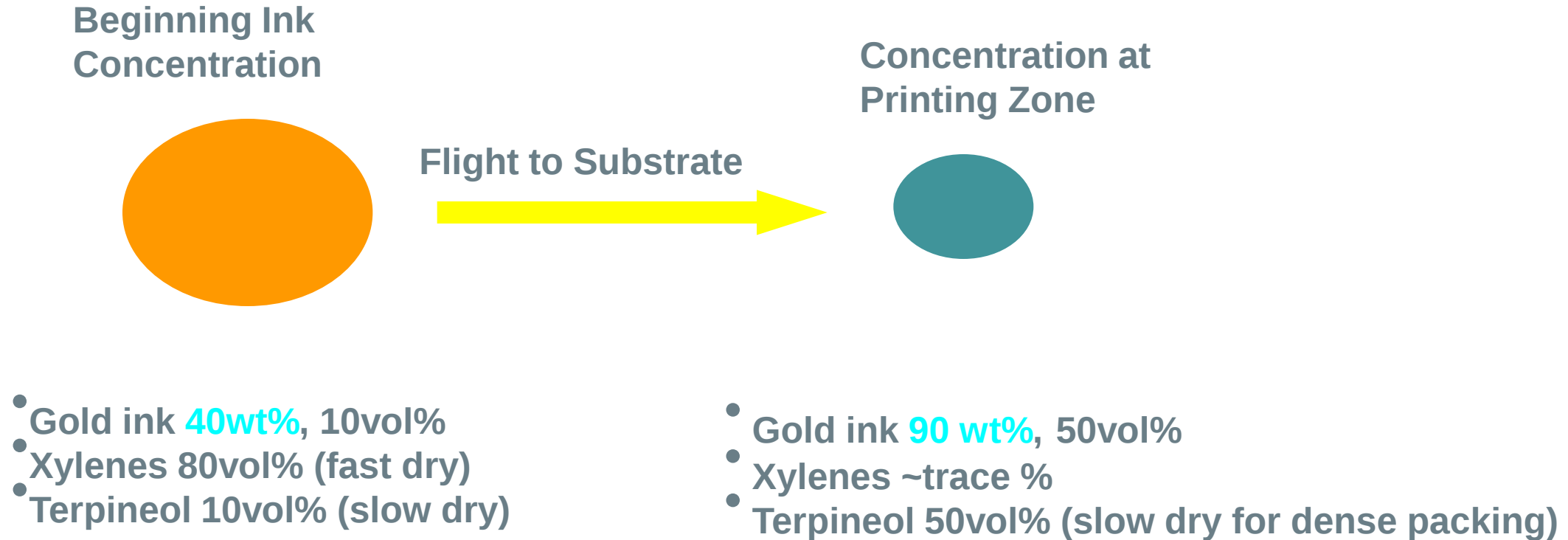
Metal Inks	Resistor Inks	Non-Metallic Conductors
Electron Inks (Ag, Au)	Acheson (carbon)	Brewer Science (SWCNTs)
Applied Nanotech (Ag, Ni, In, Cu/Ni)	Asahi (carbon)	Heraeus (PEDOT:PSS)
Advanced Nano Products (Ag)	DuPont (carbon and ruthenate)	NanoIntegris (SW & MW CNTs)
DuPont (Au)	Lord (carbon)	Chasm (SW & MW CNTs)
Henkel (Ag)	Novacentrix (carbon)	Semiconductors
PV Nanocell (Ag, Cu)	Dielectrics and Adhesives	Aldrich (organic semiconductors)
Novacentrix (Ag, Au, Cu)	HD Microsystems (polyimide)	Alfa (organic semiconductors)
Paru (Ag)	Microchem (SU8)	Merck (organic semiconductors)
Creative Materials (AgE)	DuPont (fluoropolymers)	NanoIntegris (SWCNTs)
Dycotec (Ag, Cu)	Namics (epoxy)	Reactive Chemistries
UTDots (Ag, Au, Pt)	Loctite (adhesives)	Shipley (photo and etch resists)
Xerox (Ag)	Dow (silicones)	Aldrich (acid, bases, etc.)



Why Gold Inks for Printed Electronics

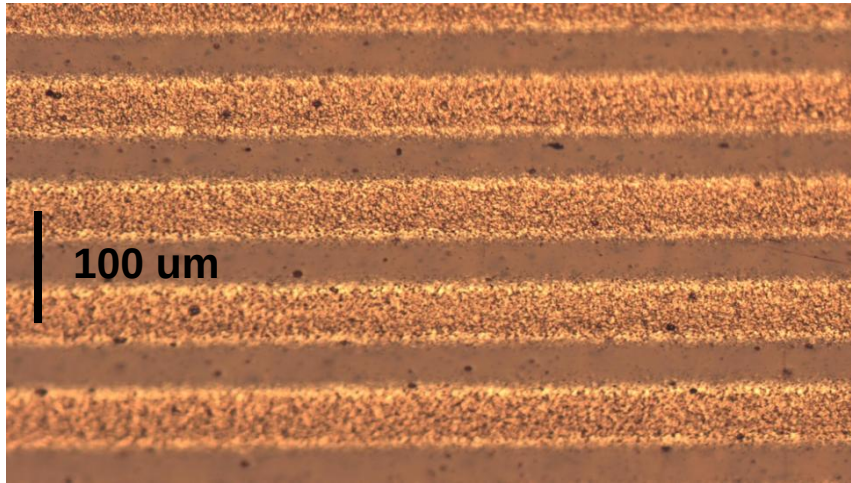
- Corrosion resistance with high operation temperature
- Low resistivity($2.2 \times 10^{-8} \Omega\text{-m}$)
- Reduced electrochemical migration at high interconnect density
- Wire bondable and solderable
- High cost but low waste with digital printing (\$0.0003/mm)
- High work function for active devices.
- Biocompatibility

Formulating Inks: Co-solvent Method

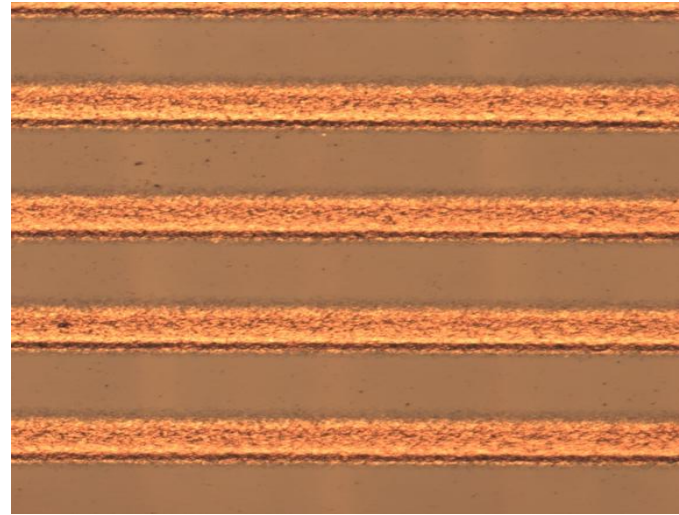


Optimal ink allows printing of high aspect ratio features with low spreading

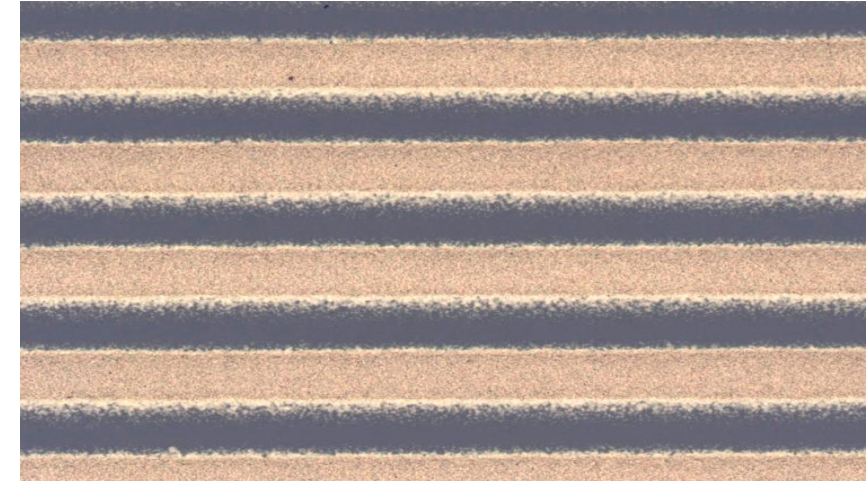
Summary of Three Gold Ink Formulations



JG-014UA on Kapton (50%w/w)
Thickness 2-3 um



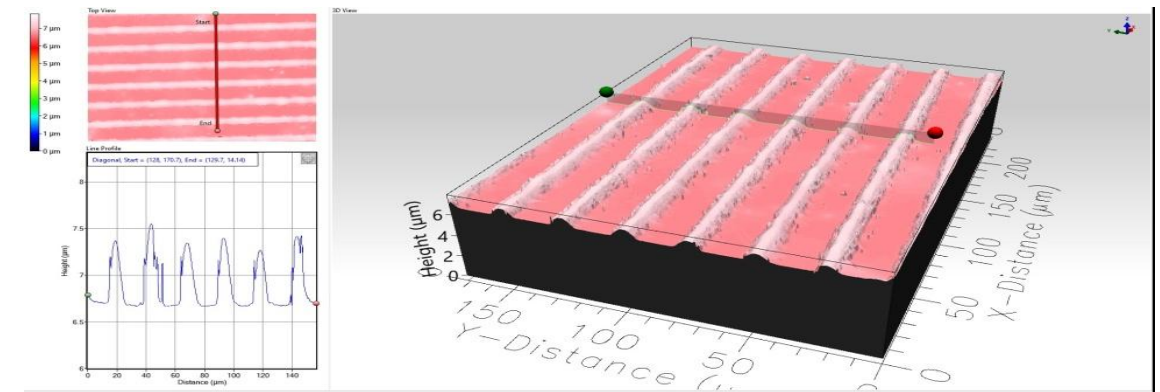
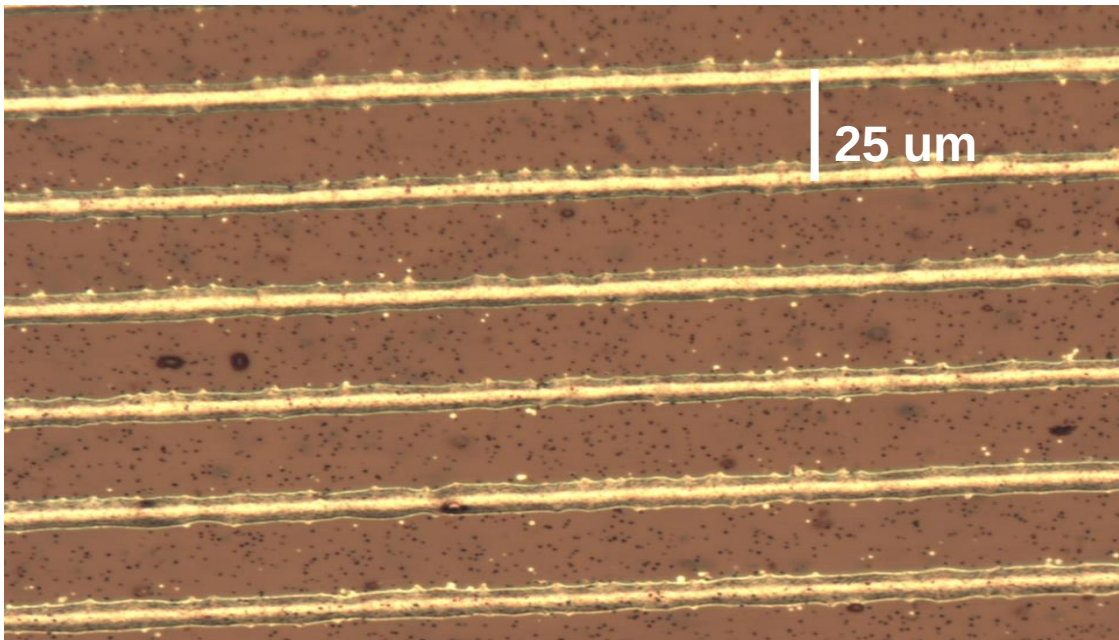
JG-024UA on Glass(40%w/w)
Thickness 1.0 um



JG-023UA on Glass(25%w/w)
Thickness 0.4 um

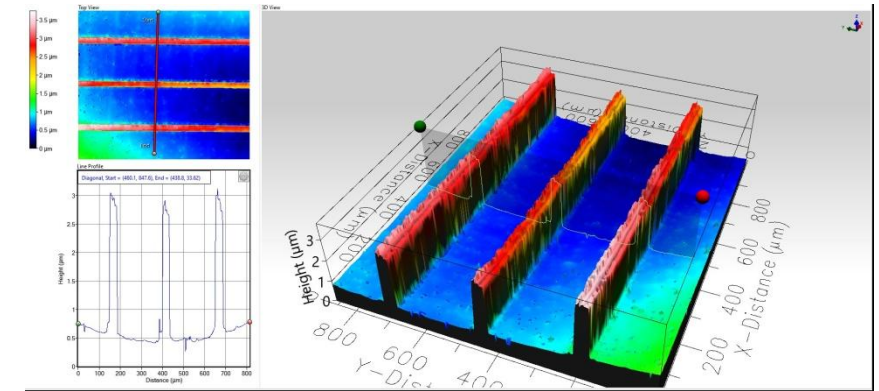
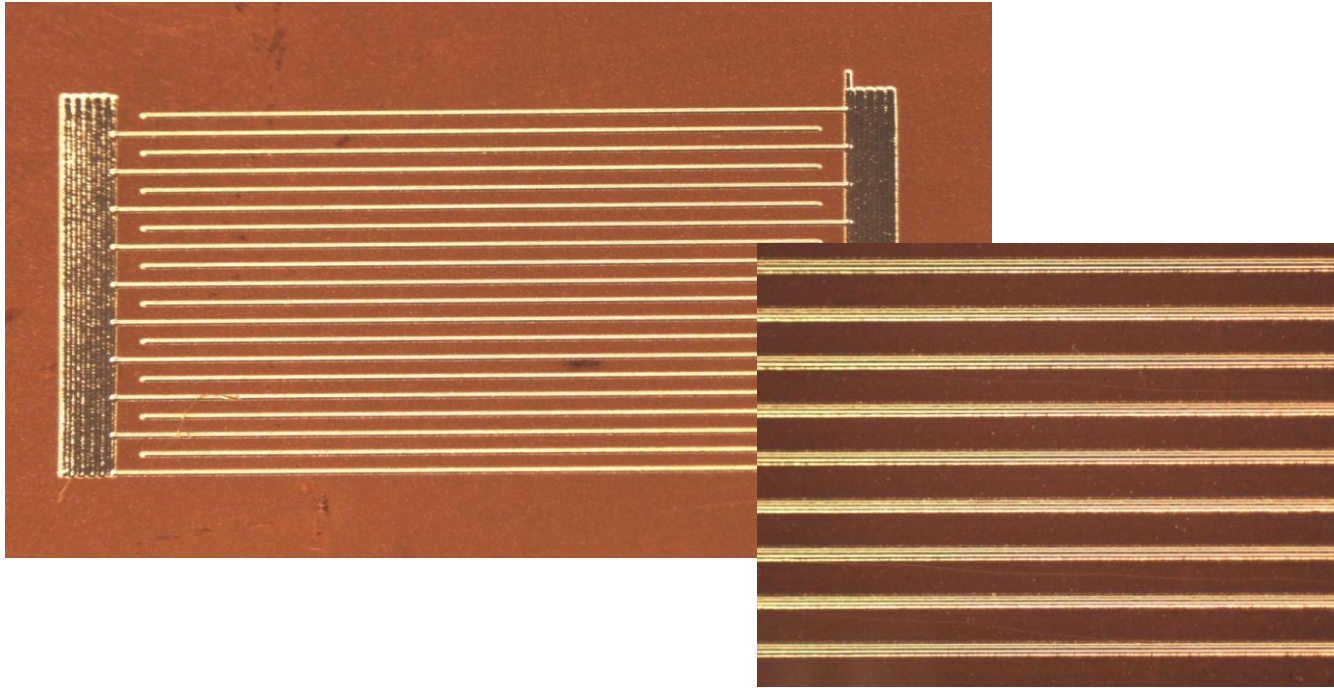
- All samples sintered at 200C overnight and printed at 5 mm/s.
- JG-014 significantly rougher, higher porosity, and lower conductivity. Not stable in the system.
- JG-023 is denser with better conductivity. But more overspray and ink spreading
- JG-024 appears to be a good compromise -- stable, good output, good conductivity, good line shape.

Feature Size Scaling



Feature sizes can be below 10 um.

Test Coupon for Line Isolation Testing ($> 10 \text{ G}\Omega$ target)

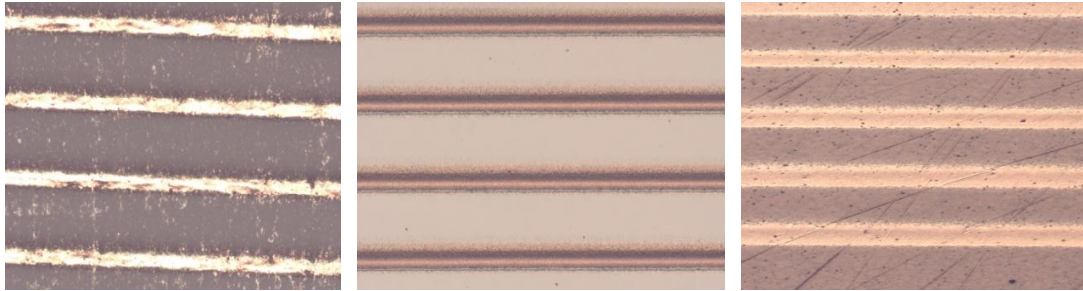


200um spacing

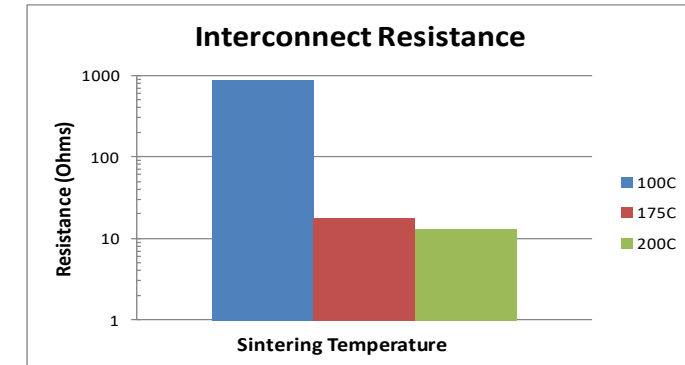
- Novacentrix JG-014 gold.
- Interdigital Electrodes as test coupon for visual overspray detection and isolation measurement.
- Ink drying rate controlled by ink additives and solvent vapor in air stream.
- Line isolation meets spec until width and space are about equal.

Sintering Strategies for Gold

Laser (832 nm)



Substrate	Laser Power (W)	Translation Speed (mm/s)	Resistivity ($\Omega\cdot\text{m}$)
Kapton	0.5	5	1.7×10^{-7}
Silicon	5	5	9.0×10^{-8}
Alumina	5	5	9.0×10^{-8}



Oven sintering (2 hrs)

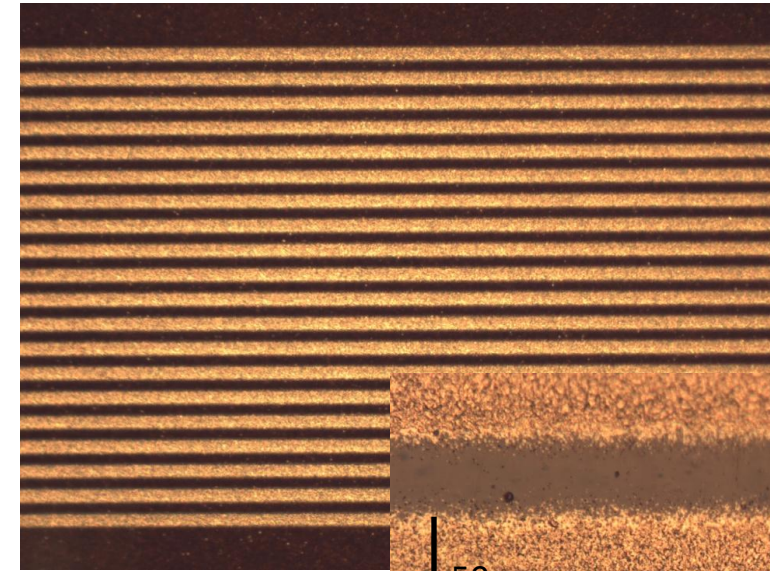
- Laser sintering roughly equivalent to sintering in oven at 250C for 2 hrs)
- Laser sintering highly dependent on thermal conductivity of substrate
- Sintering on heterogeneous substrate requires rapid power modulation to prevent substrate damage

Thermal Stability

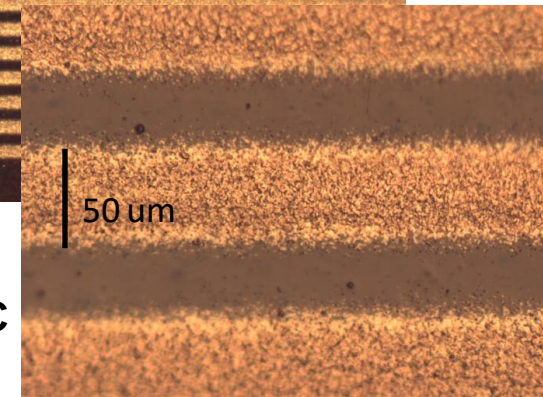
Line resistivity (Ohms/mm) and thermal reliability for 7mm long, 50 μm /50 μm L/S gold lines on Kapton.

TC -40 to +85C					
Line	R _L	R _R		R _L	R _R
1	250	239		241	222
2	250	241		244	234
3	252	242		243	236
4	252	242		247	235
5	251	242		249	234
6	252	242		246	237
7	250	244		242	237
8	253	246		241	238
9	254	244		245	239
10	251	245		232	238
Ave	251.5	242.7		243	235
STDEV	1.4	2.1		4.7	4.9

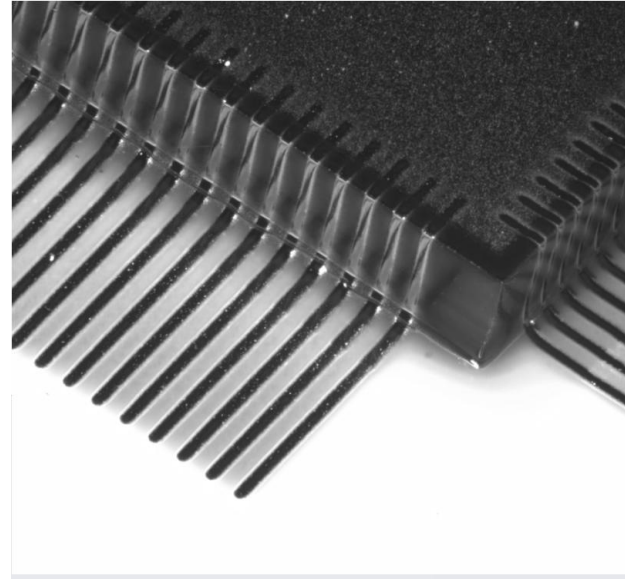
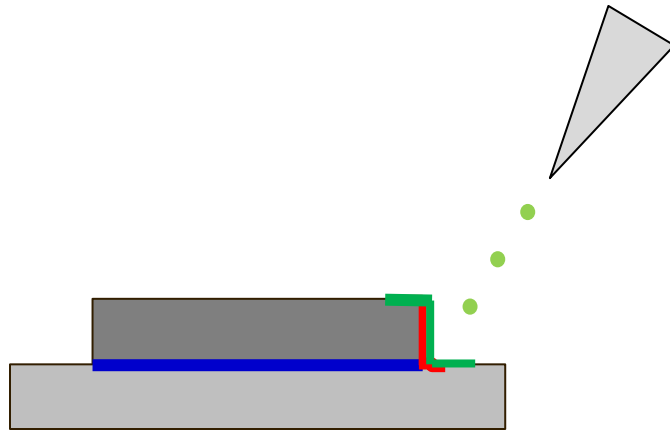
50 cycles



2 μm thickness
Sintering 2hrs@250C



Applications to 3D Interconnects



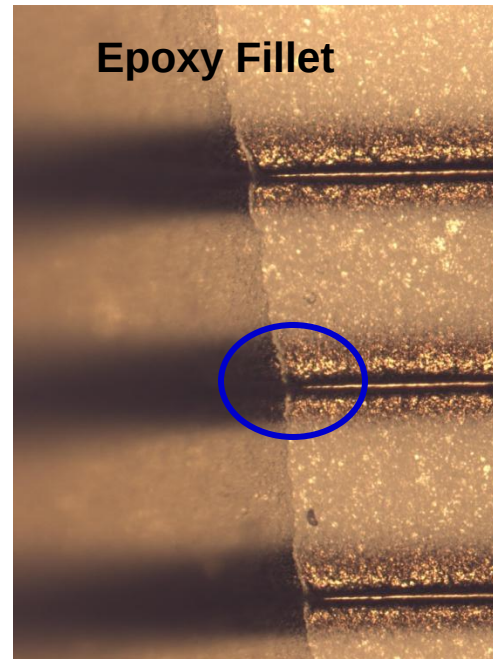
Line #	Resistance(Ω)
1	5.8
2	5.5
3	5.5
4	5.2
5	5.2
6	5.4
7	5.4
8	5.0
9	4.9
10	5.2
11	5.3
12	5.1
Ave	5.3
STDEV	0.25

- Epoxy die attach
- Polyimide sidewall coating
- Gold nanoparticle ink
- Thermal curing and sintering at 250C for 1 hr.

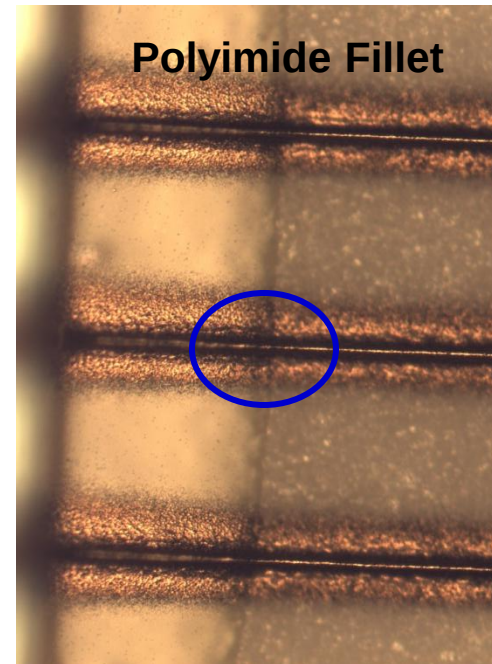
Advantages:

- Reduced package Z-height
- Higher speeds by eliminating parasitic inductive loop
- Improved reliability
- Higher interconnect density (below 50 um pitch)
- Multilevel crossovers possible

Importance of Fillet Material



Epoxy Fillet



Polyimide Fillet

Lines break during sintering due to thermal expansion mismatch

Epoxy:

Tg 45C, CTE = 211 ppm/C

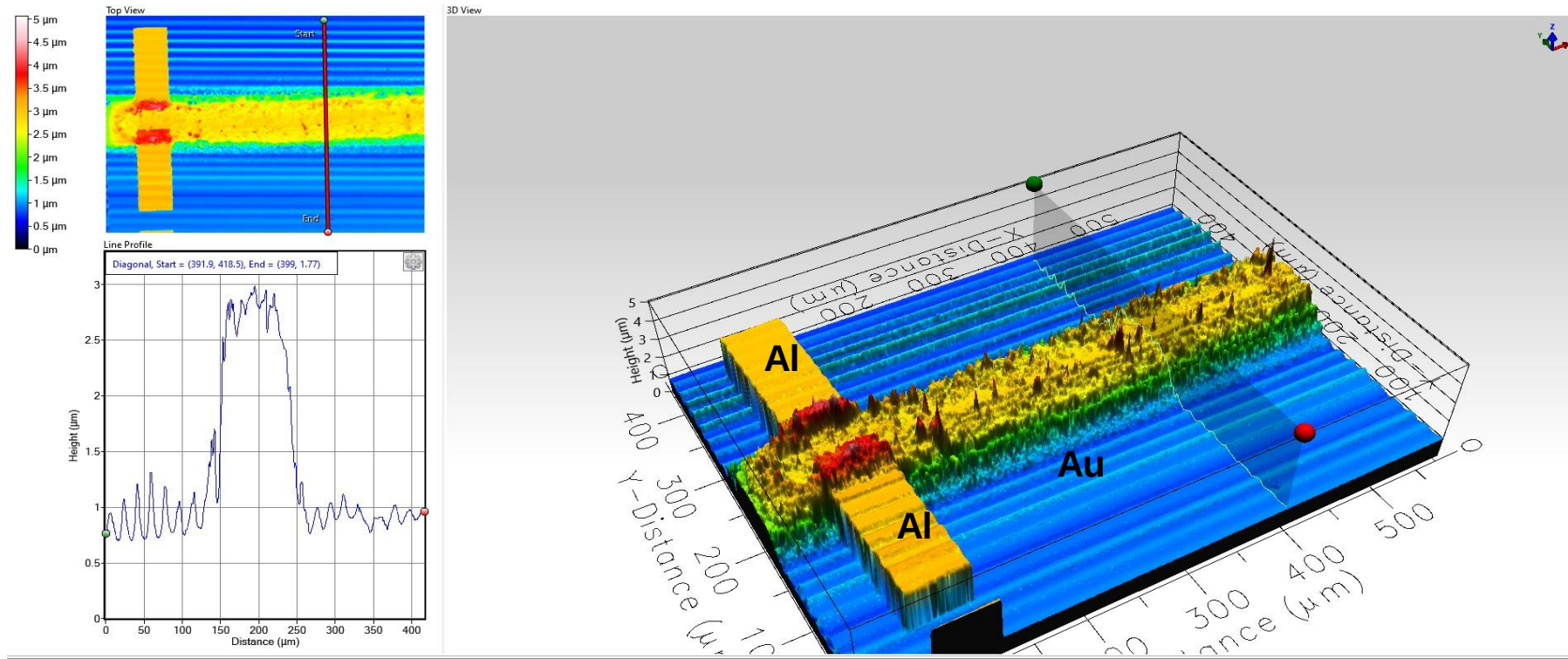
Polyimide:

Tg 300, CTE 40 ppm/C

Silicon: CTE = 2.6 ppm/C,
Alumina: CTE = 7.2 ppm/C

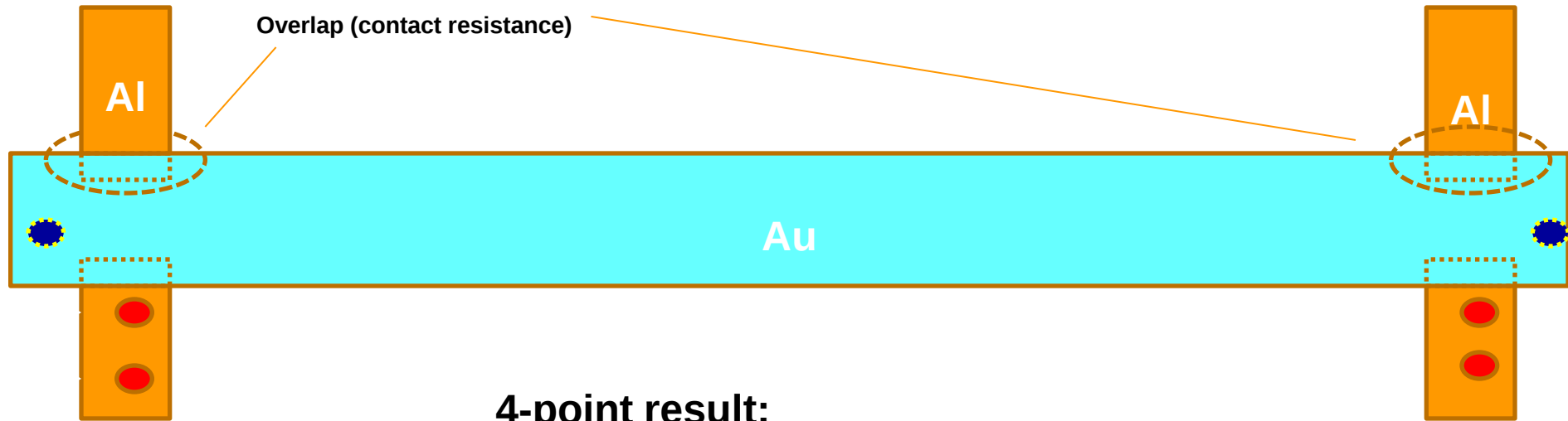
Lower CTE Polyimide is a more stable support material

Connecting to Al Bond Pads: Contact Resistance



- Native oxide on aluminum causes contact resistance
- Ammonium Hydroxide can be added to ink (25%) to etch/clean the aluminum pads
- Other reducing agents may be possible by printing separately or adding agent to ink

4- Point Test for Contact Resistance



4-point result:

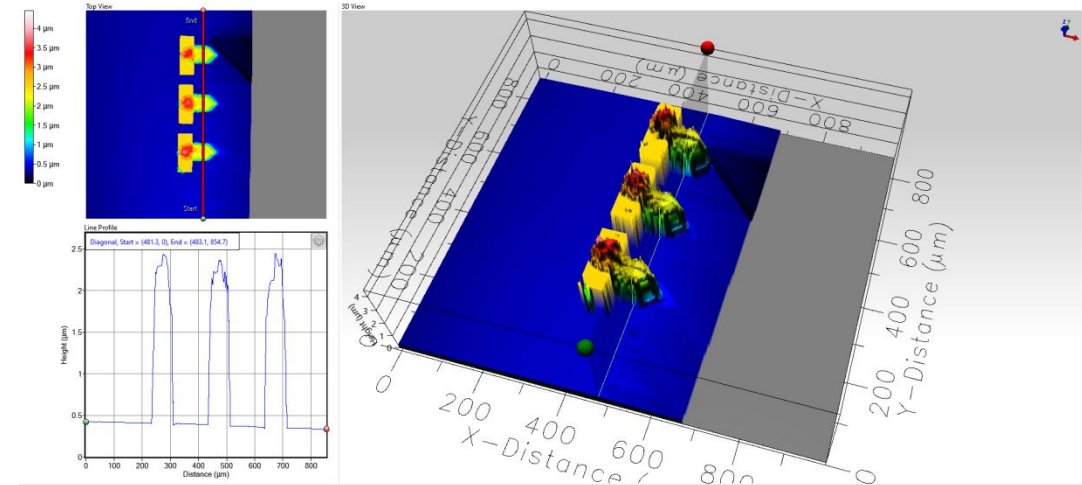
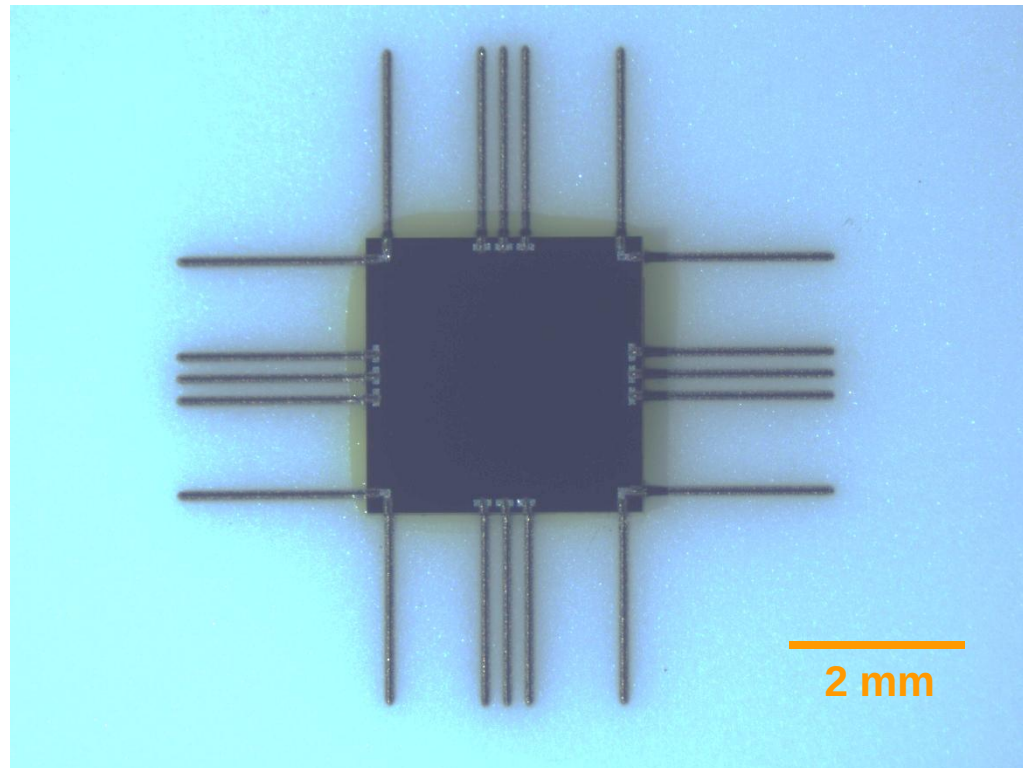
Line Resistance = 5.5Ω

Contact Resistance = 2.2Ω

Total Resistance = 9.9Ω

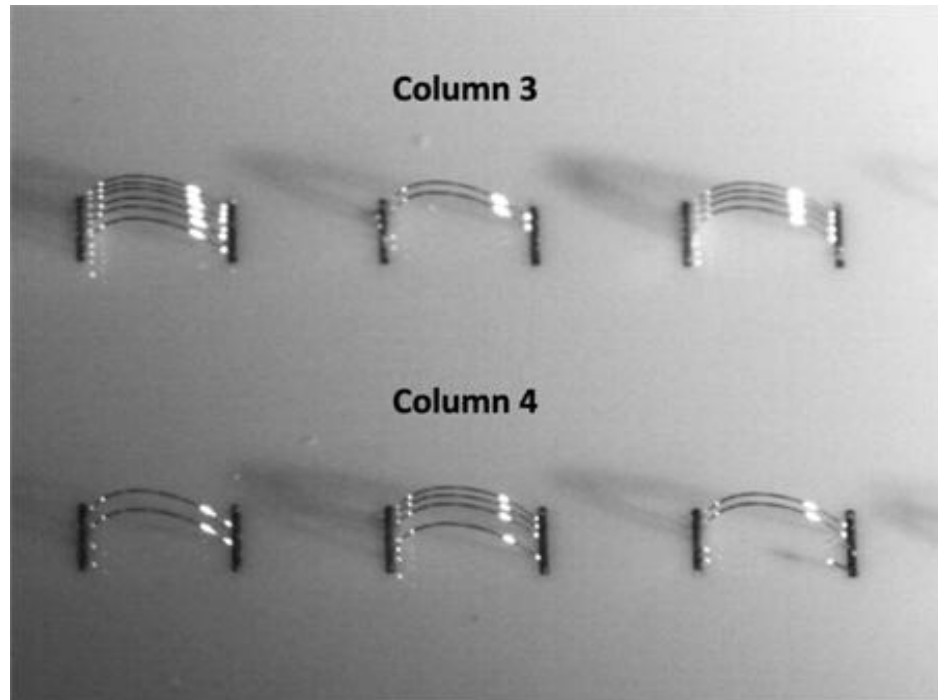
Contact resistance is comparable to line resistance

3D Connects to Aluminum Pads

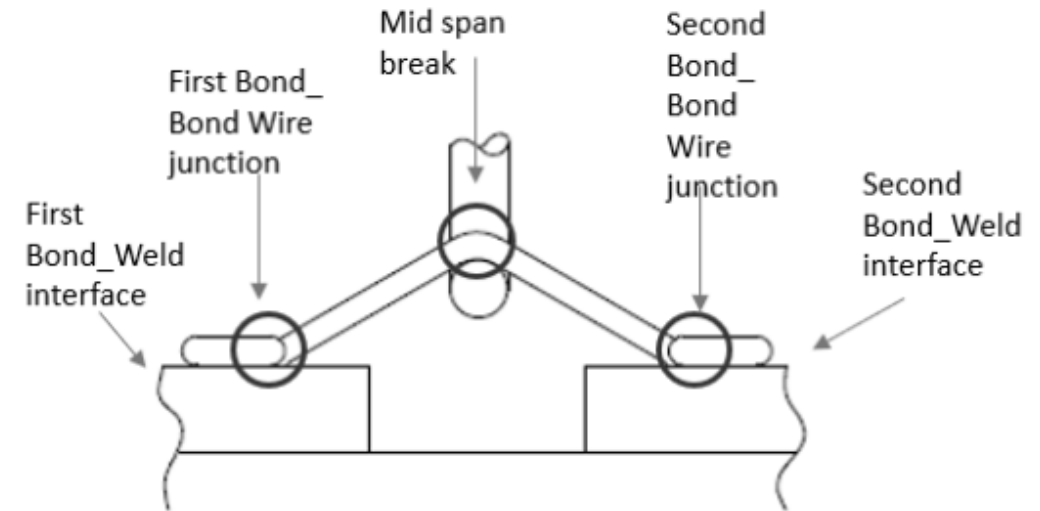


Total resistance = 5 Ohms
Contact resistance = 2 Ohms

Wirebonding to Gold



- Gold ink (Dupont QR150) printed on alumina and high fired (850C, 30 mins)
- Aluminum ribbon bonds to gold pads
- Pull test to determine bond strength and failure mode.



	Test No.	Force		Min. Accept Force	Grade Code	Grade Description	Result
33-37 A 1	1	5.194 gf		2.500 gf	9	Break in wire at neckdown on the substrate or package post.	Pass
33-37 B 1	2	6.002 gf		2.500 gf	4	Failure in bond at substrate, package post, or other than die.	Pass
33-37 C 1	3	5.296 gf		2.500 gf	9	Break in wire at neckdown on the substrate or package post.	Pass
35-39 A 1	4	5.150 gf		2.500 gf	9	Break in wire at neckdown on the substrate or package post.	Pass
35-39 B 1	5	4.328 gf		2.500 gf	9	Break in wire at neckdown on the substrate or package post.	Pass
41-45 E 1	6	3.088 gf		2.500 gf	9	Break in wire at neckdown on the substrate or package post.	Pass
41-45 F 1	7	2.770 gf		2.500 gf	9	Break in wire at neckdown on the substrate or package post.	Pass
41-45 G 1	8	4.086 gf		2.500 gf	9	Break in wire at neckdown on the substrate or package post.	Pass

Conclusions

- **Commercial Gold ink formulations optimized for Aerosol Jet.**
- **Feature sizes down to 10 um. 3D features to 25 um.**
- **Matching dielectric for mechanical support and insulation.**
- **Contact resistance to aluminum reduced by alkali clean**
- **Wire bonding to printed gold demonstrated**

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Optomec System

